

## CEE Model 200X Photoresist Spin Coater



Spinner spin-coats very uniform and thin layer of photoresist and e-beam resist on substrate even thinner than 100 nm. It can hold 5" wafer. Maximum spin speed is 12,000/minute.

### Specifications

- A virtually unlimited number of user-defined recipe program steps
- 0.1-second resolution for step times (9,999.9 seconds maximum step time)
- Spin speed: 0 to 12,000 rpm
- Spin speed acceleration from 0 to 30,000 rpm/s unloaded
- Connectivity: USB/ethernet port for communications
- Spin speed repeatability: < 0.2 rpm
- Spin speed resolution: < 0.2 rpm
- Substrate sizes: < 1 cm to 200 mm round; 7"x7" square